Accepted Manuscript

Low-temperature chemical vapor deposition (CVD) of metallic titanium film from a novel precursor

Junjie Guo, Yafeng Yang, Qingshan Zhu, Chuanlin Fan, Pengpeng Lv, Maoqiao Xiang

PII: S0257-8972(18)30889-2

DOI: doi:10.1016/j.surfcoat.2018.08.064

Reference: SCT 23733

To appear in: Surface & Coatings Technology

Received date: 10 June 2018
Revised date: 13 August 2018
Accepted date: 22 August 2018

Please cite this article as: Junjie Guo, Yafeng Yang, Qingshan Zhu, Chuanlin Fan, Pengpeng Lv, Maoqiao Xiang, Low-temperature chemical vapor deposition (CVD) of metallic titanium film from a novel precursor. Sct (2018), doi:10.1016/j.surfcoat.2018.08.064

This is a PDF file of an unedited manuscript that has been accepted for publication. As a service to our customers we are providing this early version of the manuscript. The manuscript will undergo copyediting, typesetting, and review of the resulting proof before it is published in its final form. Please note that during the production process errors may be discovered which could affect the content, and all legal disclaimers that apply to the journal pertain.



ACCEPTED MANUSCRIPT

Low-temperature chemical vapor deposition (CVD) of metallic titanium film from a novel precursor

Junjie Guo $^{a,b},$ Yafeng Yang $^{a,*},$ Qingshan Zhu $^{a,b*},$ Chuanlin Fan a, Pengpeng Lv a, Maoqiao Xiang a

^aState Key Laboratory of Multiphase Complex Systems, Institute of Process Engineering, Chinese Academy

of Sciences, Beijing 100190, China

^bUniversity of Chinese Academy of Sciences, Beijing 100049, China

*Corresponding author to: Yafeng Yang;

E-mail: yfyang@ipe.ac.cn;

Tel: +86-010-82544907

Fax: +86-010-82544907

*Corresponding author to: Qingshan Zhu;

E-mail: qszhu@ipe.ac.cn;

Tel: +86-010-62536108

Fax: +86-010-62536108

Download English Version:

https://daneshyari.com/en/article/8955667

Download Persian Version:

https://daneshyari.com/article/8955667

<u>Daneshyari.com</u>